



IEEE SW Test Workshop

Semiconductor Wafer Test Workshop

June 7-10, 2009
San Diego, CA

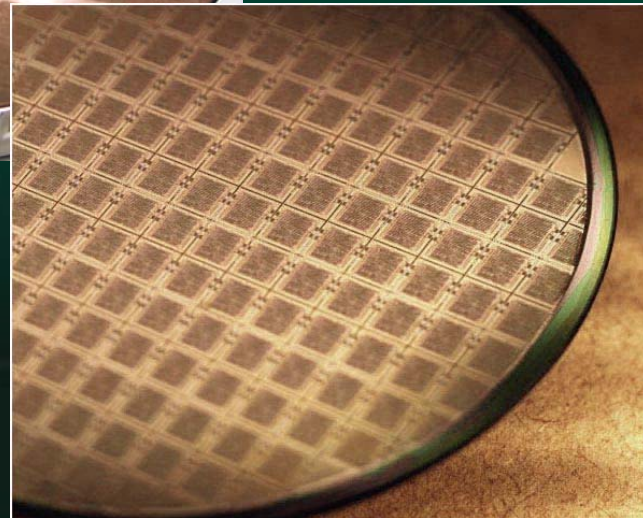
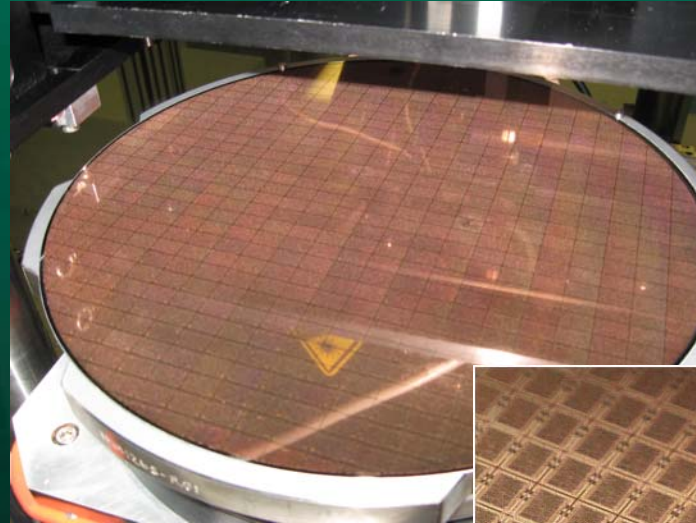
High Speed Pre-Probe Wafer Inspection



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Pre-Probe Inspection Probe Card Protection



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Introduction

- **Offering an inspection strategy to enable pre-screening of wafers prior to probing to avoid probe card damage .**
- **Focus is on MEMS-type of one touch down 300mm probe cards for the memory makers.**
- **Elimination of costly probe card damage.**



Focus → Probe Card Type

- High density DUT probe cards
- One Touch Down probe card
- High parallelism probing
- Costly probes given $> 50,000$ contacts
- Pad pitches down to 60uM
- → MEMS type card



Objective

- **Create an alternative inspection process for users of MEMS probe cards enabling process flow throughputs.**
- **100% wafer screening while minimizing handling and time out of WIP.**
- **Mitigating the risk of damaging expensive probe cards caused by interaction with large debris on wafer.**

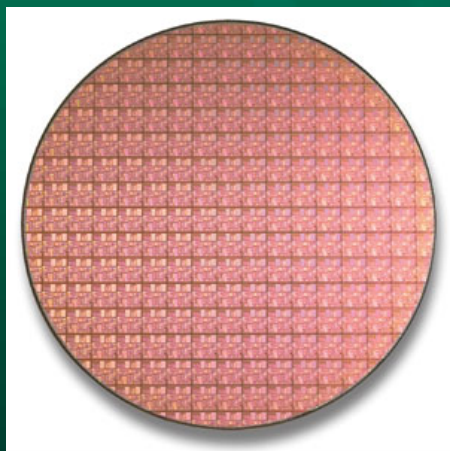


Customer's Challenge

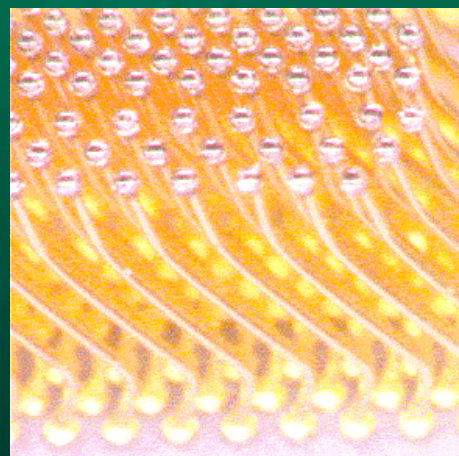
- **Memory manufacturing is a low margin high volume manufacturing endeavor.**
- **DRAM manufacturing is not profitable on wafer sizes smaller than 300mm.**
- **High throughput and yield are imperative for making profits in memory. One touch down probe cards are the choice for speed and CoO.**
- **They cannot afford to damage these cards in the testing process. Capital investment is high.**



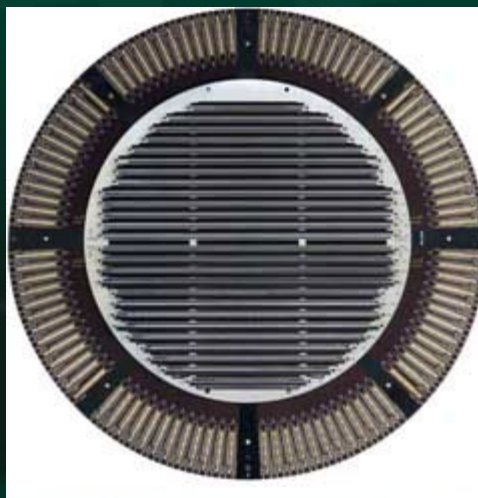
Associated Costs



WIP Loss



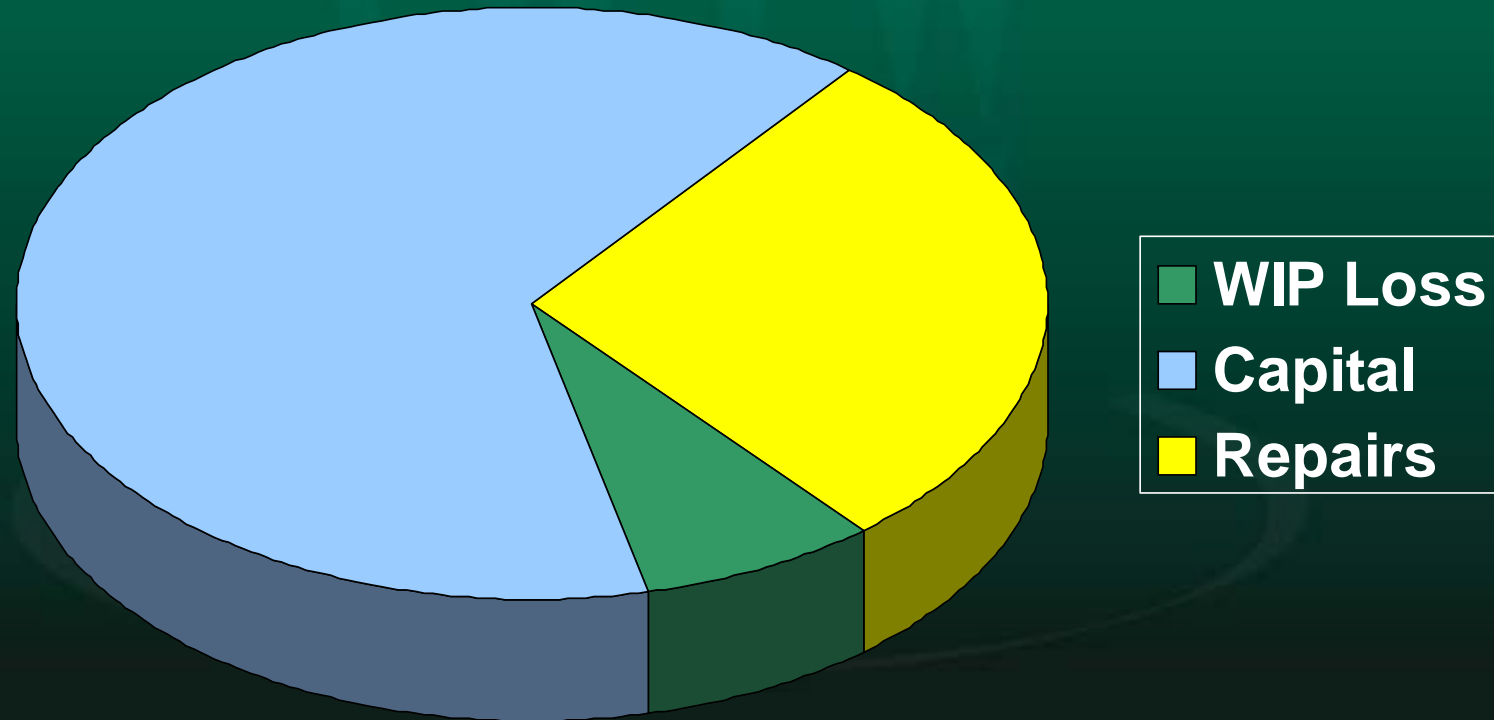
Repair



Capital



ROI Target → Capital Savings



Customer Data



2D Inspection Strategies

- **Die to golden image comparison.**
- **Relatively high speed.**
- **Catches only defects based on X-Y information. No Z information.**
- **Decision process:**
 - Reject if X-Y data shows large defect
 - If defect meets certain X-Y criteria, revisit with 3D inspection to verify defect (debris) is above height thresholds.

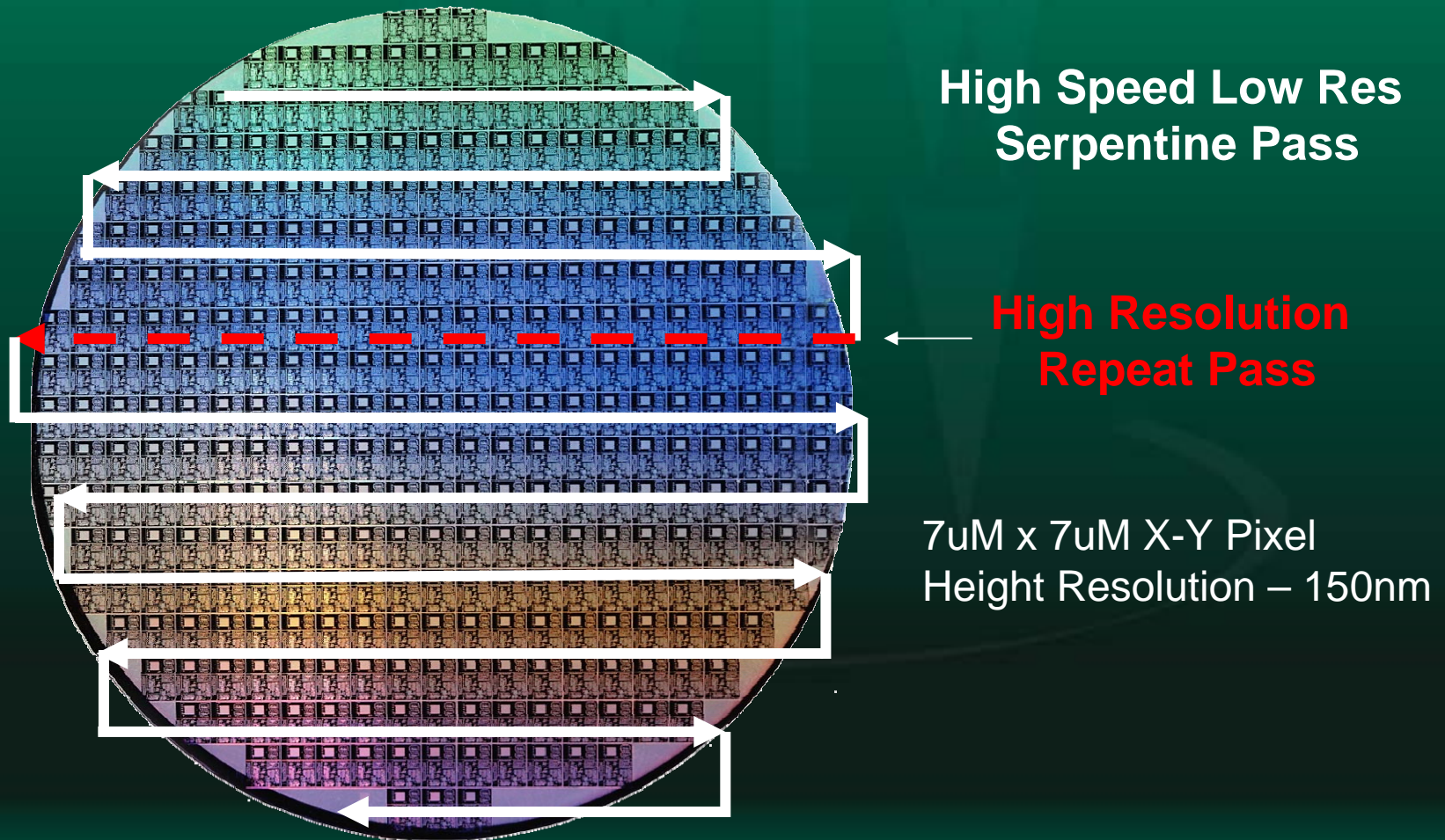


2D-3D Methodology

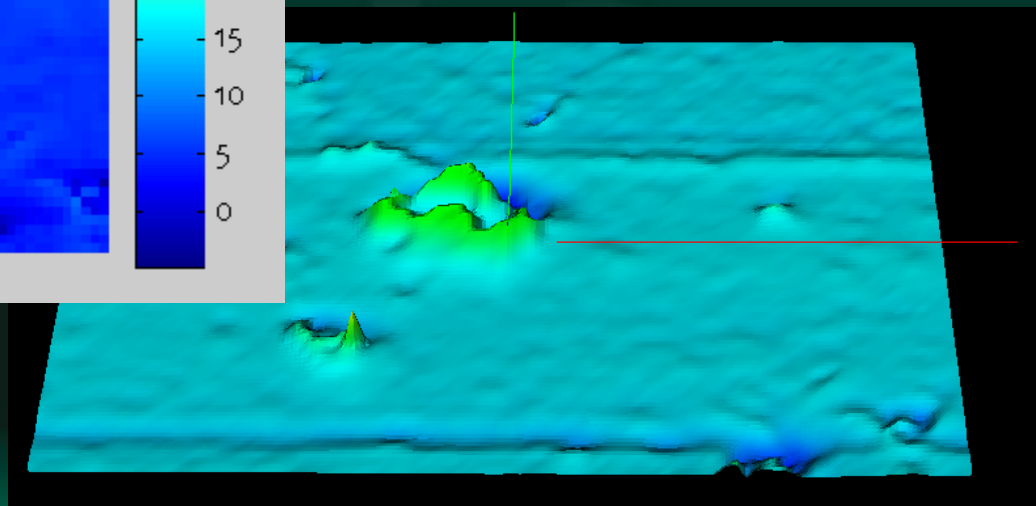
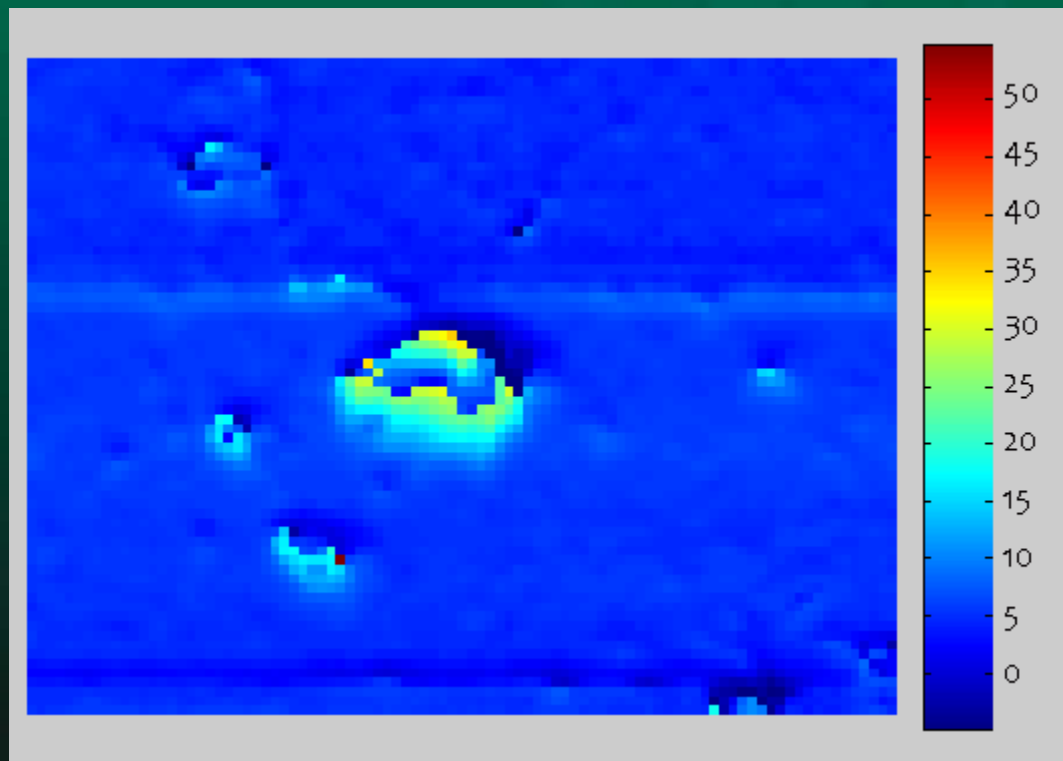
- **Straight down perspective on wafer.**
 - No Shadows; full view of defect
- **No moving parts on inspection head.**
 - High reliability
- **Simultaneous 2D and 3D measurements.**
- **High speed low resolution inspection for screening, row / column re-inspection for high resolution characterization of suspect debris.**



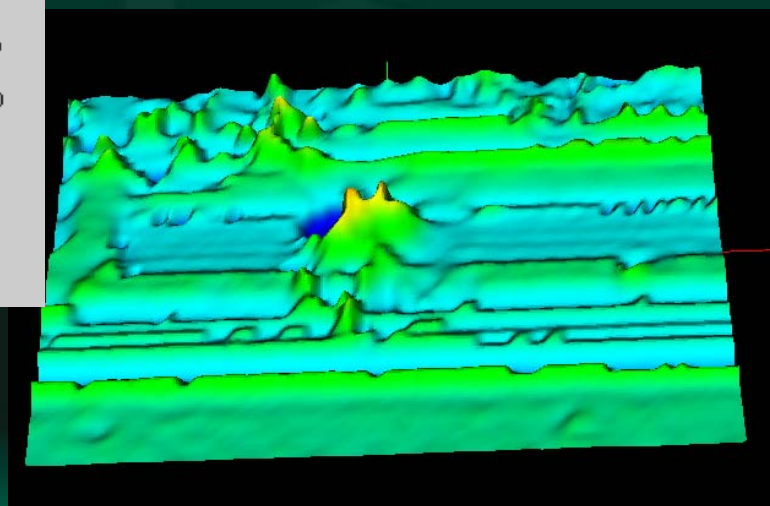
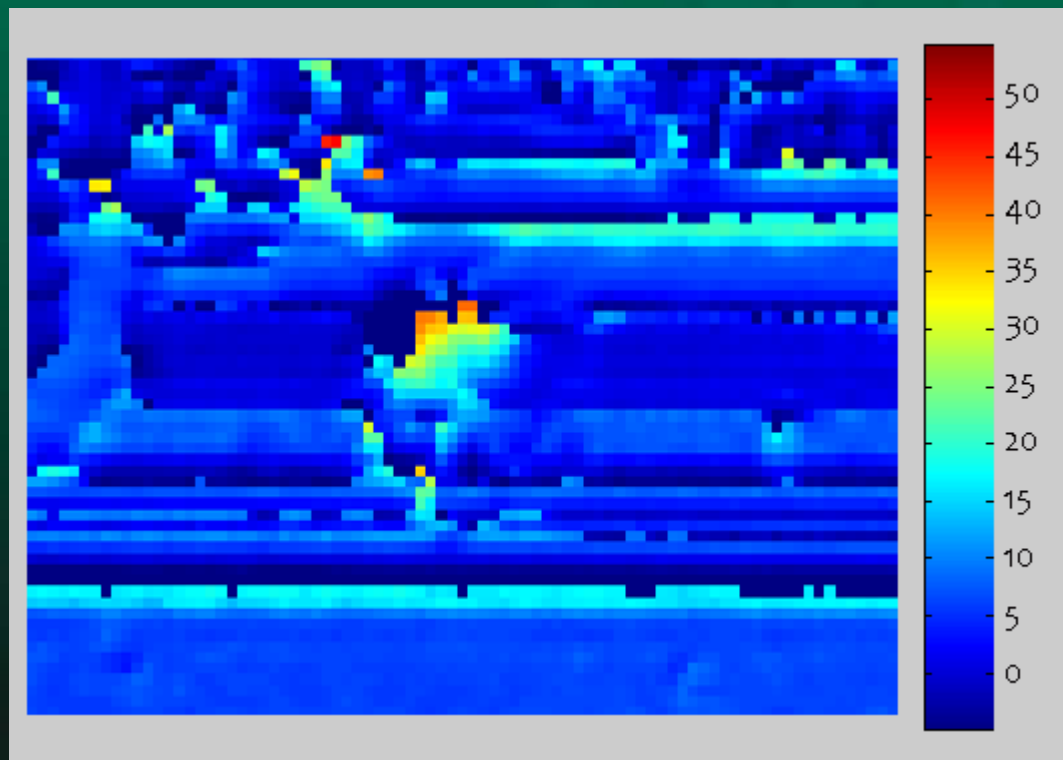
2D-3D Metrology Methodology



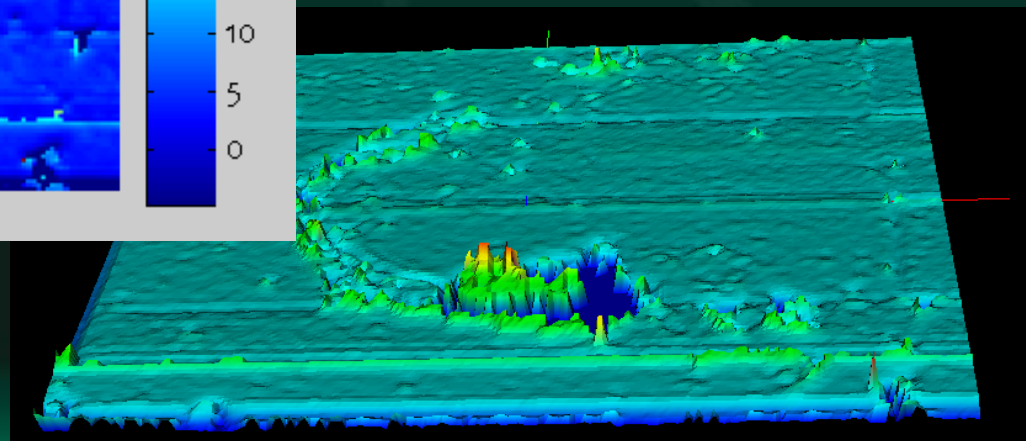
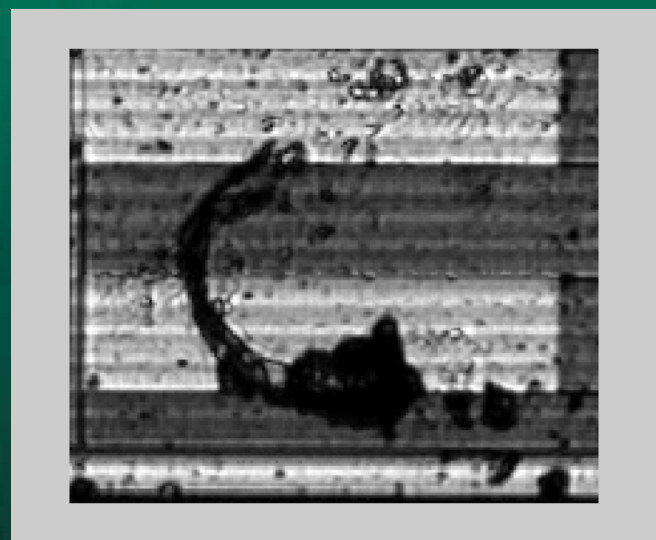
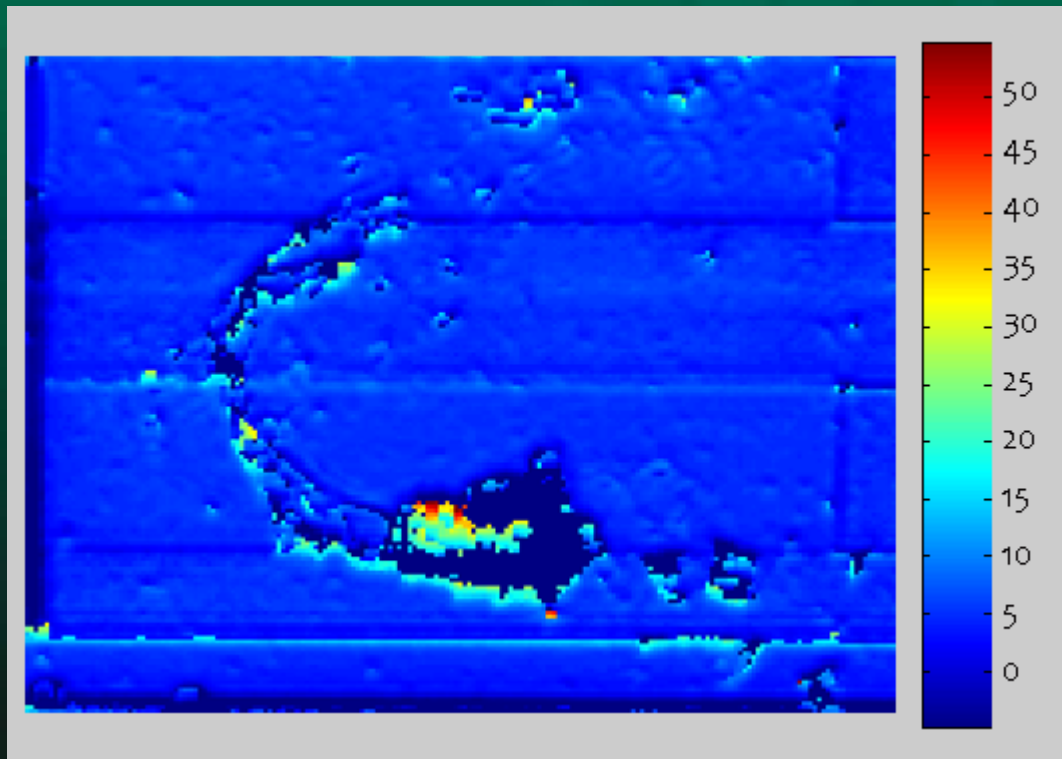
Inspection Metrology / Images



Inspection Metrology / Images



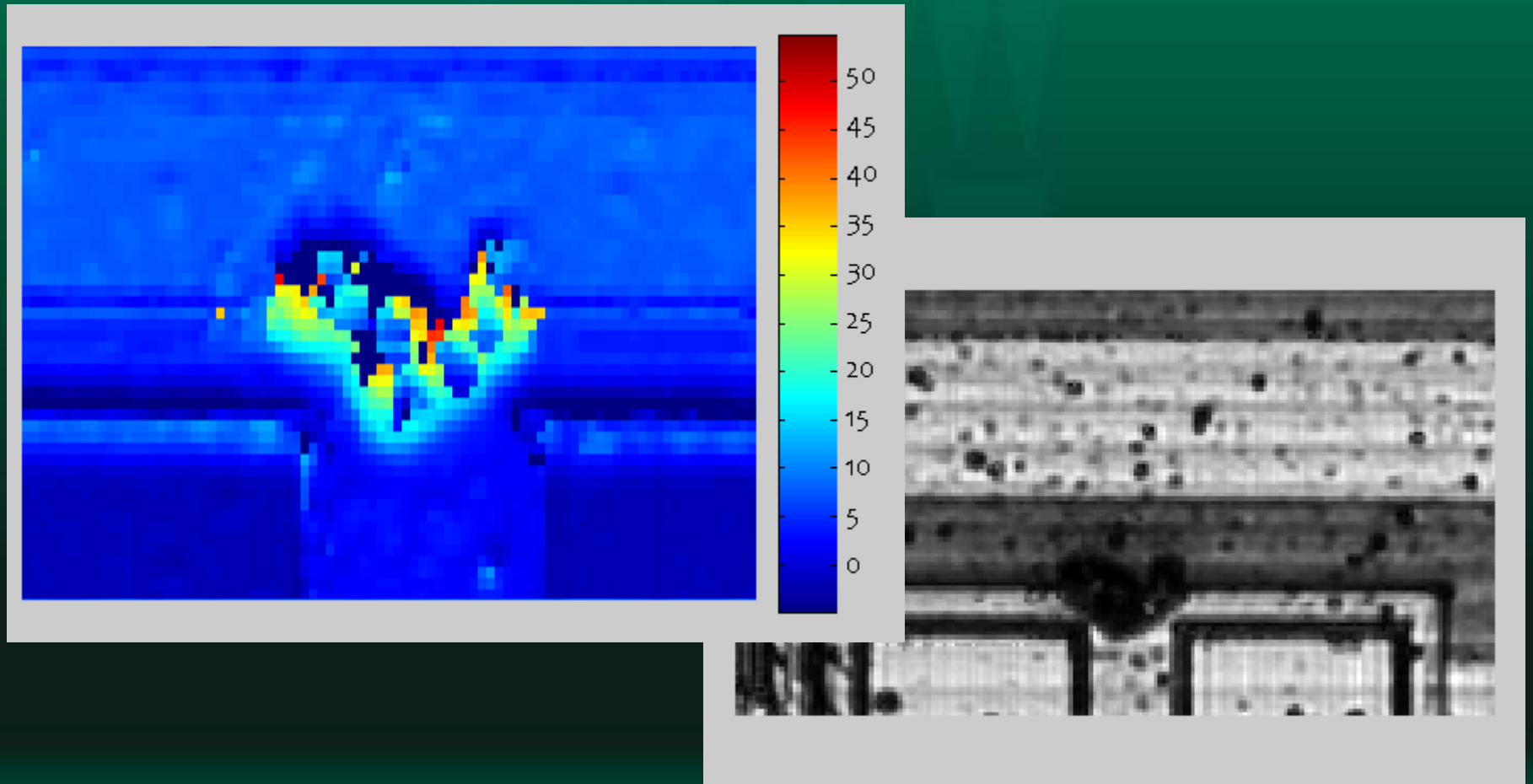
Inspection Metrology / Images



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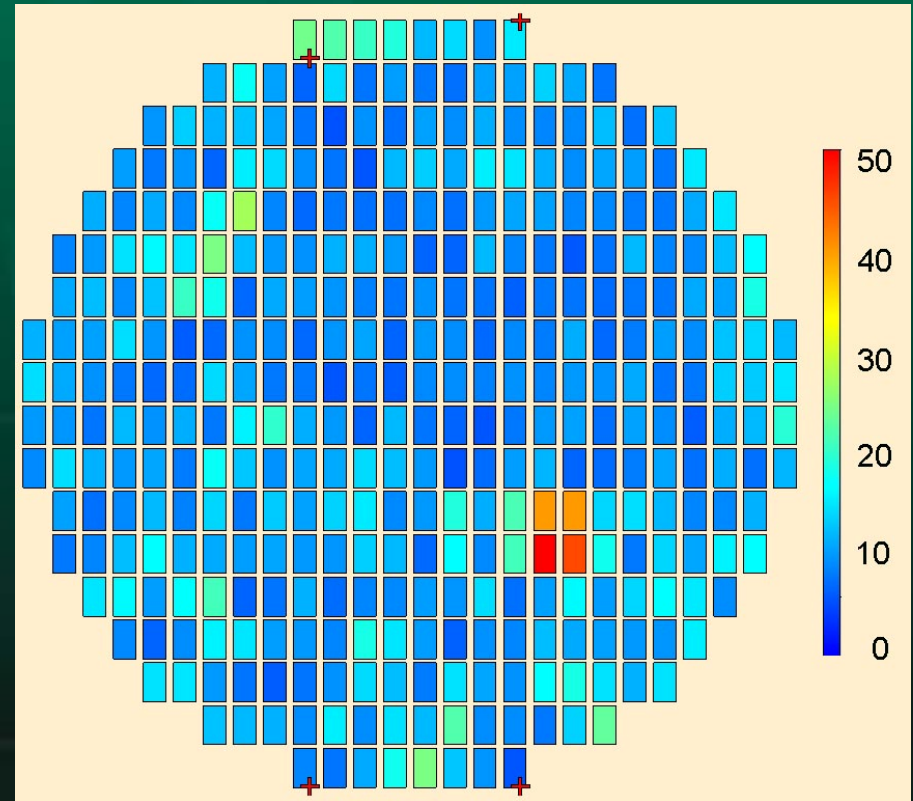
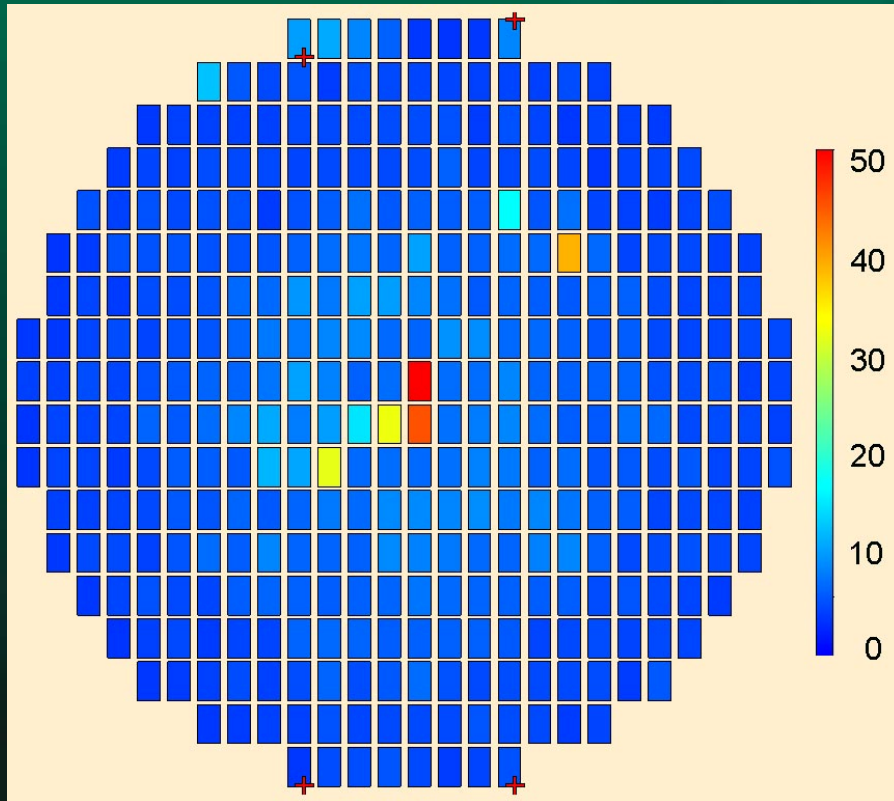


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Particle Height Wafer Maps



300mm Memory Wafer Die Map showing Max Particle Heights (μm)



Strengths / Weaknesses

- This is a solution to eliminate the risk of damaging probe cards which can be expensive.
- Capital outlay for this 2D-3D inspection solution is >\$750k. ROI could vary in time significantly depending on fab methodology.
- Throughput for this application:
 - 300mm wafers
 - 100% inspection with up to 20% high resolution 3D revisit
 - 100+ WPH
- System would be configured for pre-probe inspection only. Other applications would require H/W changes and optional S/W.



Thank You



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